

**Reduction in Step Height Variation and Correcting Contrast Inversion in Dynamic AFM of
WS₂ Monolayers**

Supplementary Figures

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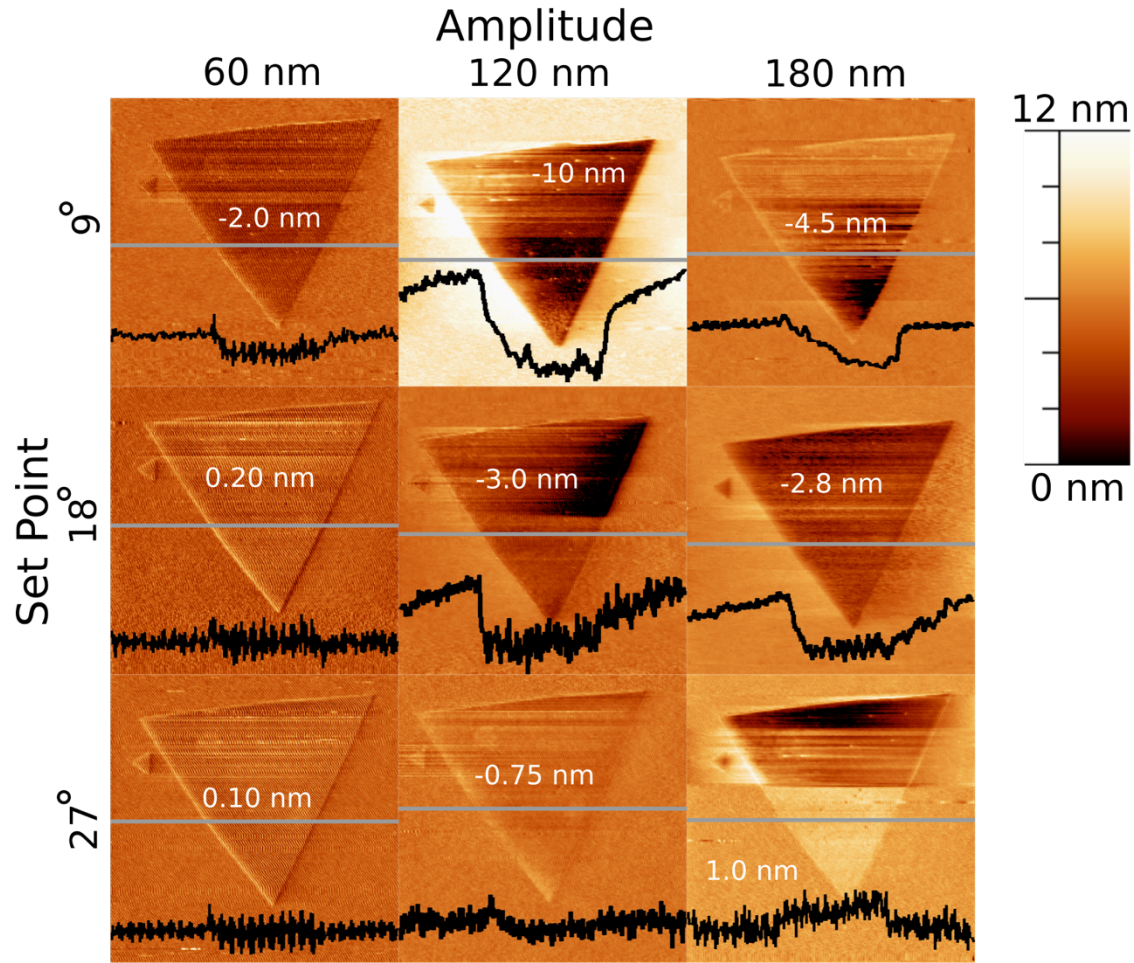


Figure S1: AFM topographic images of annealed CVD WS₂ monolayers on SiO₂. The WS₂ appears inset into the substrate except at low amplitudes and high set points. The bottom right image (180 nm, 27°) shows a switching of contrast mid-scan, attributed to operation near the bistability. This is in contrast to the results for the same experiment performed on as-grown samples shown in Figure 1a, where high amplitudes produce correct contrast.